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(12) **United States Design Patent** (10) **Patent No.:** **US D931,241 S**  
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(54) **LOWER SHIELD FOR A SUBSTRATE PROCESSING CHAMBER**

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(\*) Notice: This patent is subject to a terminal disclaimer.

(\*\*) Term: **15 Years**

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(52) **U.S. Cl.**  
USPC ..... **D13/182**

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USPC ..... D13/118, 133, 162, 182, 184, 199; D15/144.1, 144.2, 150, 199; D23/213; D24/232  
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See application file for complete search history.

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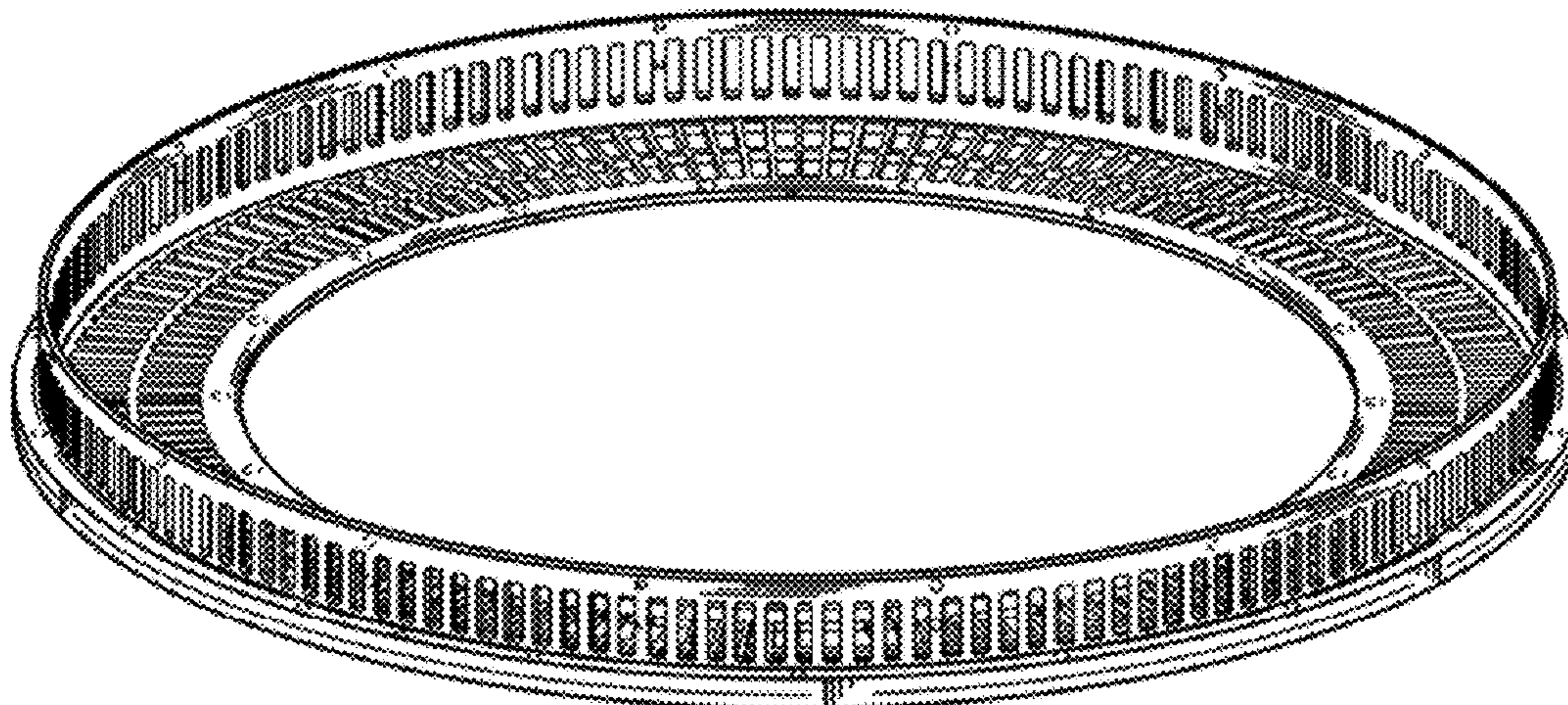
(57) **CLAIM**

The ornamental design for a lower shield for a substrate processing chamber, as shown and described.

**DESCRIPTION**

FIG. 1 is a top isometric view of a lower shield for a substrate processing chamber, according to the novel design. FIG. 2 is a top plan view thereof. FIG. 3 is a bottom plan view thereof. FIG. 4 is a front elevation view thereof. FIG. 5 is a back elevation view thereof. FIG. 6 is a right side elevation view thereof. FIG. 7 is a left side elevation view thereof; and, FIG. 8 is a cross-section view taken along line 8-8 in FIG. 2.

(Continued)



The dashed lines in FIGS. 1-8 are for the purpose of showing environmental structure, and form no part of the claimed design.

**1 Claim, 5 Drawing Sheets**

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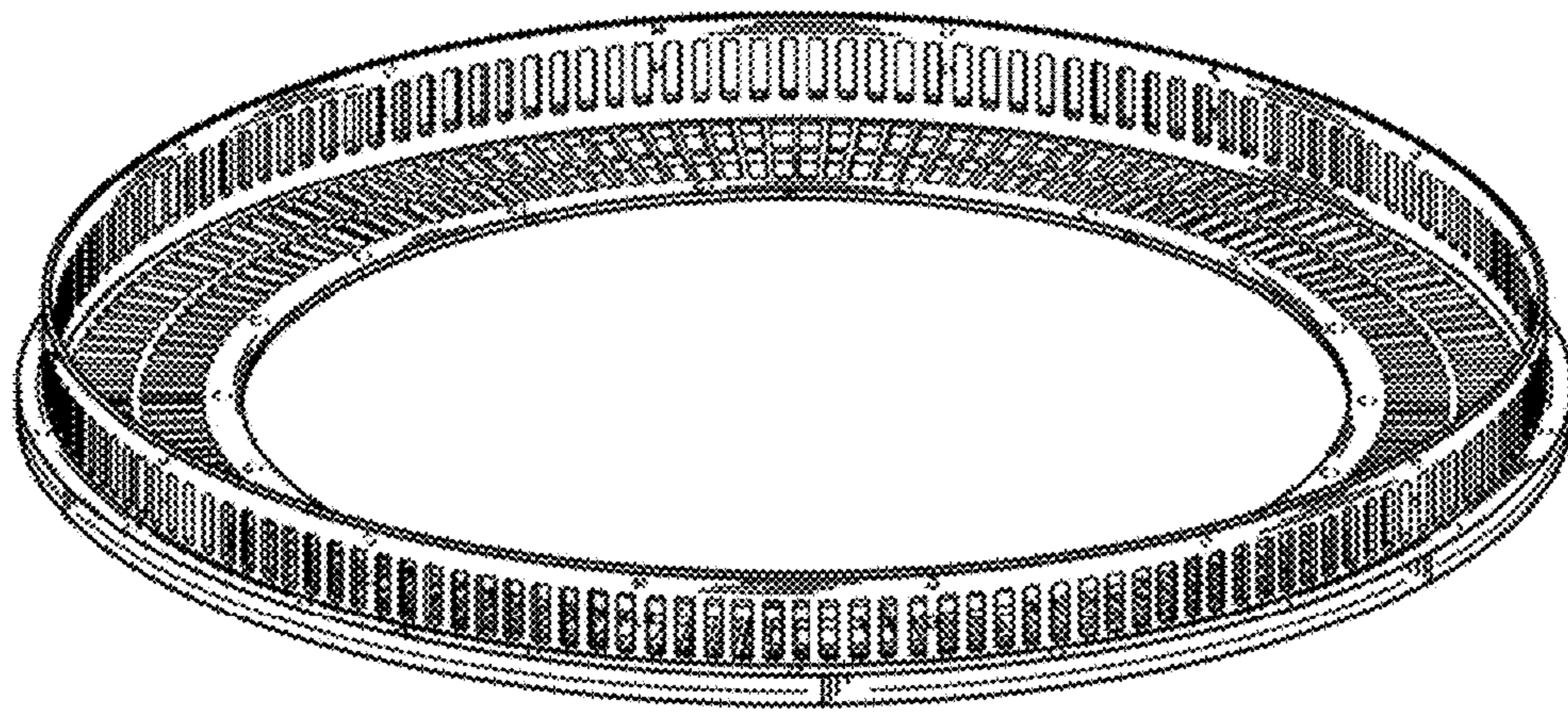


FIG. 1

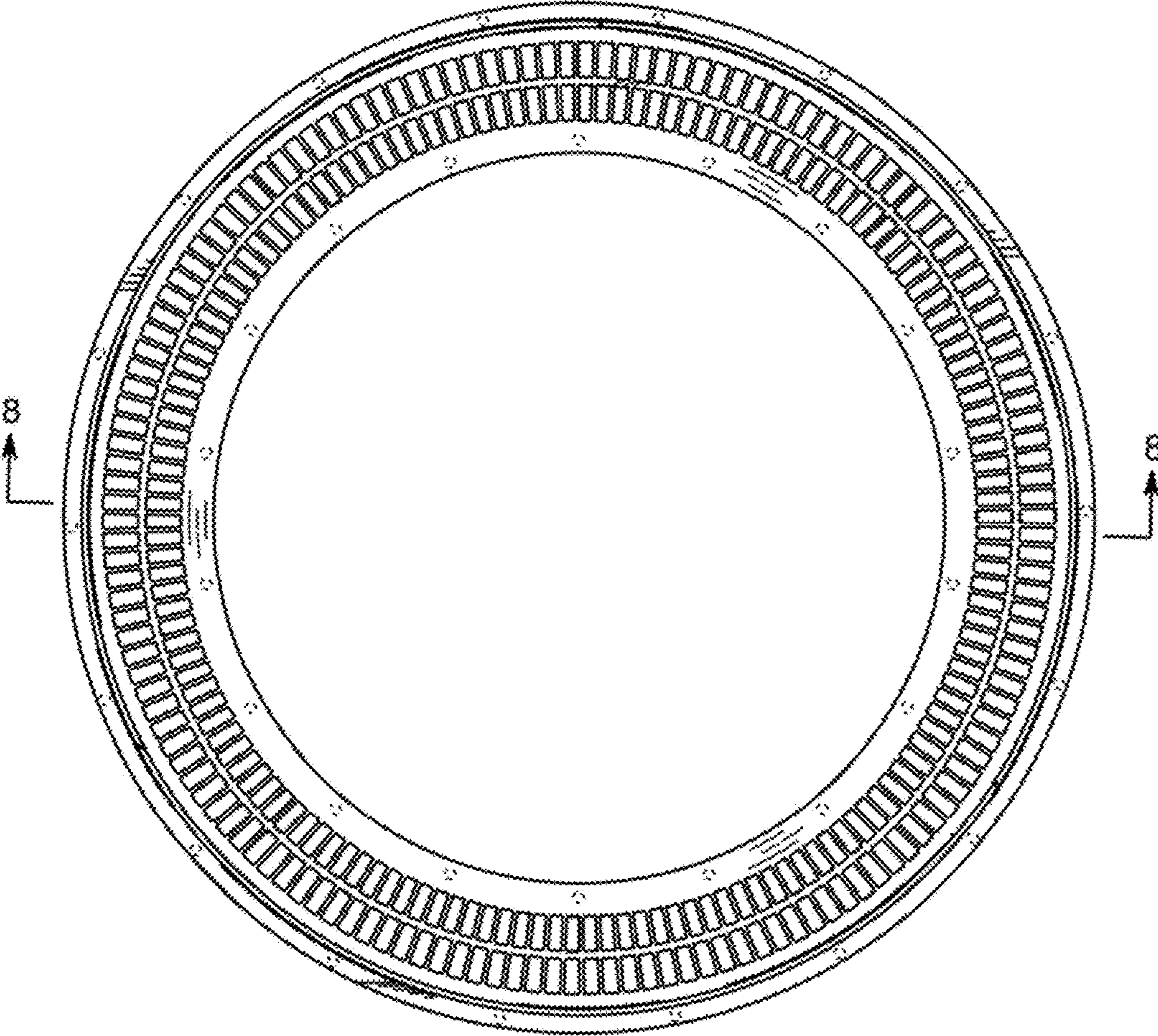


FIG. 2



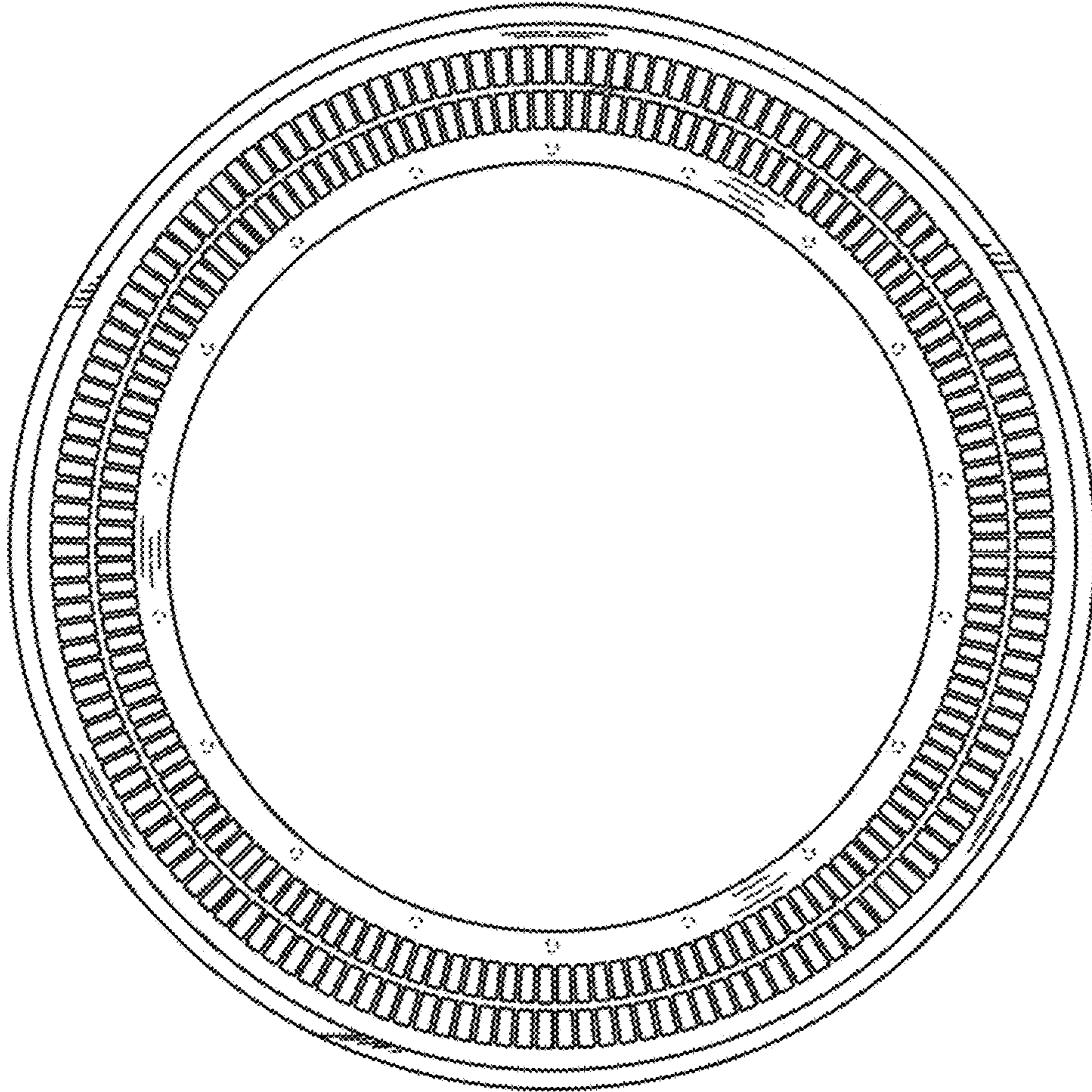


FIG. 3

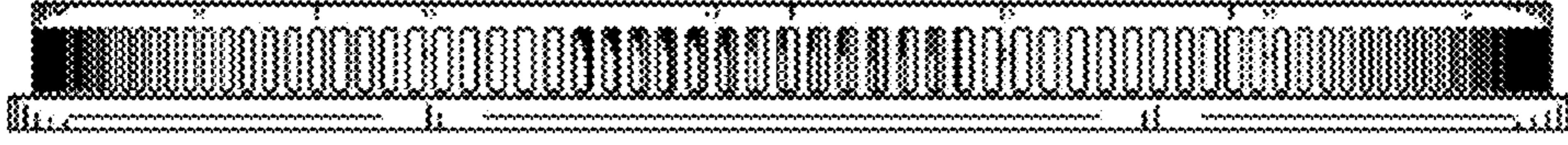


FIG. 4

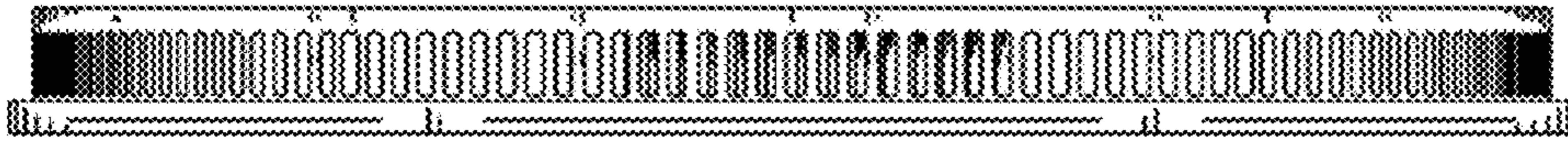


FIG. 5



FIG. 6



FIG. 7

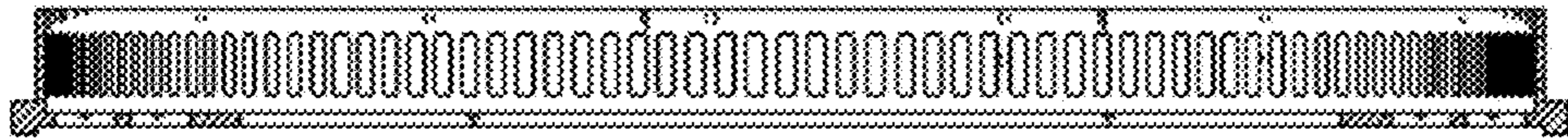


FIG. 8